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# First-principles investigations on the electronic structures of U<sub>3</sub>Si<sub>2</sub>



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#### ABSTRACT

 $U_3Si_2$  has been widely utilized as a high-power uranium fuel for research reactors due to its high density of uranium. However, theoretical investigations on this material are still scarce up to now. For this reason, the computational study via density functional theory (DFT) is performed on the  $U_3Si_2$  compound in this work. The properties of  $U_3Si_2$ , such as stable crystalline structures, density of states, charge distributions, formation energy of defects, as well as the mechanical properties are explored. The calculation results show that the  $U_3Si_2$  material is metallic and brittle, which is in good agreement with the previous experimental observations. The formation energy of uranium vacancy defect is predicted to be the lowest, similar with that of UN. The theoretical investigation of this work is expected to provide new insight of uranium silicide fuels.

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#### 1. Introduction

The uranium silicide compound has been licensed as a dispersion type fuel in an aluminum matrix by the Reduced Enrichment for Research and Test Reactors (RERTR) Program since 1988 [1–3]. Nowadays, uranium silicide dispersion fuels have been widely utilized and their safe operation has been confirmed by many applications worldwide, mostly with low enriched uranium (LEU, below 20 wt% <sup>235</sup>U) and for uranium densities up to about 4.8 gU/cm³ [4,5]. As the mostly utilized uranium silicide, U<sub>3</sub>Si<sub>2</sub> has been applied to reduce enrichment in the existing research reactors [4]. Relative to U<sub>3</sub>Si, U<sub>3</sub>Si<sub>2</sub> has been identified to be more stable with the growth of fission-gas bubble at high uranium loading in the fuel meat and burnups, and slower in interaction layer growth between uranium silicide and aluminum [6]. Up to now, plenty of research has been carried out in order to characterize the behaviors of the

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U<sub>3</sub>Si<sub>2</sub> and other uranium silicide compounds that may be options as nuclear fuels. For example, Gan et al. [7] reported the microstructure of the irradiated U<sub>3</sub>Si<sub>2</sub>/Al silicide dispersion fuel. They found the irradiated U<sub>3</sub>Si<sub>2</sub>/Al dispersion fuel consists of uniformly distributed fission gas bubbles in U<sub>3</sub>Si<sub>2</sub> particles. The estimated average diameter, number density and volume fraction for small bubbles (<1  $\mu m)$  in the fuel particle are ~94 nm, 1.05  $\times$   $10^{20}~m^{-3}$ and ~11%, respectively. Kim et al. [6] compared the interdiffusion of U<sub>3</sub>Si<sub>2</sub>-Al, U<sub>3</sub>Si-Al and USi-Al under irradiation and pointed out that the interaction layer growth rates do not decrease with the decreasing U/Si ratio caused by fission. U<sub>3</sub>Si<sub>2</sub> has been also studied in great detail on the crystal structure, and magnetic, electronic and thermal properties. Dwight [8] examined the structure of U<sub>3</sub>Si<sub>2</sub>. which is determined to be a primitive tetragonal structure of the Cu<sub>3</sub>Au-type with ten atoms per unit cell. It is also found that U<sub>3</sub>Si<sub>2</sub> is a brittle material with a high melting point at 1665 °C. Remschnig et al. [9] have reported the magnetic behavior of U<sub>3</sub>Si<sub>2</sub>, and they noticed that the susceptibility of U<sub>3</sub>Si<sub>2</sub> has a slight linear dependence on temperature between 5 K and 300 K. Thus they deduced that U<sub>3</sub>Si<sub>2</sub> is a paramagnetic material. Miyadai et al. [10] also found that the U<sub>3</sub>Si<sub>2</sub> is a Pauli paramagnetic metal at low temperature, in

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good agreement with Remschnig's results [9]. Berche et al. [11] performed a detailed thermodynamic study of the U-Si system in which they provided a series of data on the enthalpies of formation for the U-Si compounds. Yagoubi et al. [12] have studied the structural and electronic properties of USi and USi2 under high pressure using both experimental and theoretical methods. By experimental investigation, they found that USi and USi<sub>2</sub> can keep their crystal structure under high pressure without any noticeable phase transition. This is in good agreement with their calculated results. In their further computational study, the bulk modules of USi and USi<sub>2</sub> are also predicted. Yang et al. [13] investigated the physical properties of binary uranium silicide alloys by means of density functional theory (DFT) calculations and the structures, elastic properties and the Debye temperature of several U-Si compounds are determined theoretically. Chen et al. [14] have reported their theoretical prediction on the electronic structure of two-dimensional uranium silicide thin film with the plane-wave basis pseudopotential.

Numerous efforts have been devoted in the experimental and theoretical investigation on the uranium silicide up to now. However, the report on the computational study on U<sub>3</sub>Si<sub>2</sub> at the electronic structure level has barely been mentioned in the literature. In order to gain a deep insight into the electronic structures for U<sub>3</sub>Si<sub>2</sub>, which are valuable in the evaluation for the safety and lifetime of the U<sub>3</sub>Si<sub>2</sub> fuel, it is necessary to conduct theoretical calculations on the U<sub>3</sub>Si<sub>2</sub> compound. In this paper, we present our theoretical investigations on the structures, mechanical properties, and the defect formation energies of U<sub>3</sub>Si<sub>2</sub> by the first principles DFT method. Our results may provide theoretical support on the industrial application of the uranium silicide fuel.

#### 2. Methods

In this work, the theoretical calculations are performed based on the density function theory [15,16], using the VASP code [17] with the projector-augmented-wave method. In regard to the exchange correlation potential, the PBE functional [18] is utilized within the generalized gradient approximation (GGA). Due to the strong onsite Coulomb repulsion among the localized U 5f electrons, we use the Hubbard (DFT + U) approximation to estimate the strong correlation effect [19]. In this paper, the cut-off energy of planewave is 500 eV and a  $9 \times 9 \times 9$  Monkhorst-Pack [20] k-point mesh is adopted. The geometries of the U<sub>3</sub>Si<sub>2</sub> system are optimized with the force criterion of 0.02 eV/Å, and the total energy is relaxed until the energy difference is smaller than  $10^{-5}$  eV. In the calculations of defect formation energy, the 2  $\times$  1  $\times$  2 supercells containing 40 atoms are constructed so that the boundary effect on the formation of defects can be negligible, and the K-point for the supercells are chosen to be  $2 \times 2 \times 2$  with consideration of both the accuracy and the computational cost.

#### 3. Results and discussions

#### 3.1. The crystal structures of U<sub>3</sub>Si<sub>2</sub>

The compound  $U_3Si_2$  has a tetragonal structure, and there are ten atoms in the conventional unit cell with the space group of P4/mbm, as shown in Fig. 1. The structure is obviously of  $Cu_3Au$ -type with a U atom located in the Cu site and a pair of Si atoms in the position of the single Au atom. In order to examine the ground-state properties of  $U_3Si_2$ , we calculated the stable crystalline structures by the DFT + U scheme as adopted in the studies of many other uranium nuclear fuels , such as  $UO_2$ , UN, UC and etc. [21–23]. The U value employed in this work is determined systematically by using different U values to predict the lattice parameters of  $U_3Si_2$ 

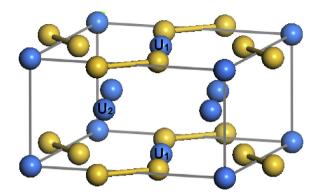
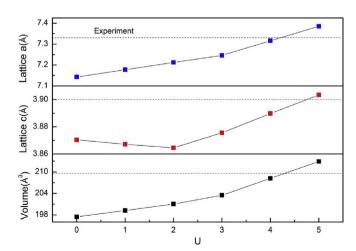


Fig. 1. The crystal structure of U<sub>3</sub>Si<sub>2</sub>.

and comparing them with experimental observations. The experimental and calculated lattice constants are both displayed in Fig. 2. If the calculations are conducted without the Hubbard correction, (U = 0.0), the predicted lattice constant of a is significantly lower than the experimental one (7.14 Å vs 7.33 Å), which is a reflection that Hubbard correction is a necessary procedure for the improvement of prediction on the U<sub>3</sub>Si<sub>2</sub> system. According to this work, it is found that when U equals to 4.0 eV, the calculated lattice constant (a = b) and the total volume of the unit cell are the closest to the experimental values (lattice a: 7.32 Å vs 7.33 Å [8]; volume: 208.20  $\text{Å}^3$  vs 209.63  $\text{Å}^3$  [8]). Hence, in this paper the physical properties of  $U_3Si_2$  are all estimated by the GGA + U (U = 4 eV) approach. As shown in Fig. 1, there are two types of U atoms in a unit cell of U<sub>3</sub>Si<sub>2</sub>, which are denoted as U<sub>1</sub> and U<sub>2</sub> in the figure, respectively. The U<sub>1</sub> atoms are neighbored by Si atoms in the (001) lattice plane of the unit cell. While, the atoms U<sub>2</sub> are located in the (002) plane where only U atoms are present.

From this work, the calculated bond distances of U—Si are from 2.847 to 2.971 Å. The distances of the shortest U—U and Si—Si bonds are found to be 3.308 and 2.386, respectively. The bond lengths of our optimized structures are in accord with the experimental values [24]. According to the interatomic distances, covalent bonds are formed between the two adjacent silicon atoms and the interactions between U and Si atoms are probably ionic bonding. The U—U distance is close to the value of weak bonds in the metallic uranium [25], which may imply that the U—U interaction is likely a



**Fig. 2.** The lattice parameters a and c  $(\mathring{A})$  and the volume  $(\mathring{A}^3)$  of the unit cell of  $U_3Si_2$  predicted with different U values in the GGA + U calculations. The experimental values are shown as the horizon dash line.

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